**Research Scientist**

**Job description:**

Perform chamber scale modeling using software like HPEM to test and optimize plasma properties to assist new hardware design in etch chambers. Work on zero to 3D profile modeling to optimize current etch process conditions and propose new operation regimes or process conditions. Collaborate with headquarter customer support and R&D teams to pursue possible solutions for any critical issues that customers are currently facing and will be facing in the near future. Conduct basic process development work to validate modeling assumptions in a clean room environment.

**Qualifications:**
• PhD in Electrical Engineering, Chemistry, Physics, Material Science or related Engineering Fields with graduate training on chamber and feature scale plasma modeling is required.
• 3+ years Semiconductor Etch plasma/process modeling is required.
• Desire background in Process characterization and data analysis including Design of experiments [DOE].
• Excellent verbal and written communication skills a must.
• Must be fluent in English.
• Must be able to work in teams as well as individually.
• Ability and desire to work as a part of a multicultural team.
• Some travel, <20% is required in year 3 and beyond.